## Aka-Brief #14 Cast Iron

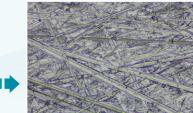












Times are stated for a 300 mm preparation system and Forces for an individual 40 mm dia. sample.

On a 250 mm system the times should be increased by 30%, on a 200 mm system by 100%.

With larger samples the force should be increased, with smaller samples decreased.

Time and Force may vary depending on the equipment.

\* Step 4 is optional.

BF, 200x

BF, 200x

BF, 200x

\*\* Oxide polishing gives a scratch free result but introduces some relief. To minimize relief, this step can be replaced by a final step using DiaUltra 1 µm on a Napal cloth.

\*\*\* For water-sensitive samples, only diamond polishing is recommended using water-free suspensions/lubricants for the 3 and 1 µm steps. The use of water should also be avoided for cleaning after those preparation steps.



Piatto 220

Water



35 N



Until plane





35 N



Allegran 3 9 µm

DiaUltra

150 rpm









2:30 min







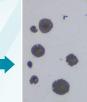
DiaUltra 3 µm



150 rpm













Chemal



Colloidal Silica 50 nm Alkaline\*\*





150 rpm

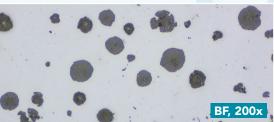






20 N

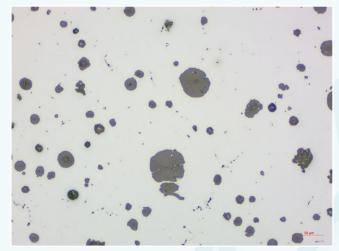


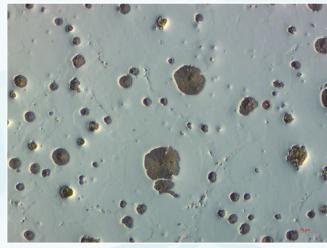


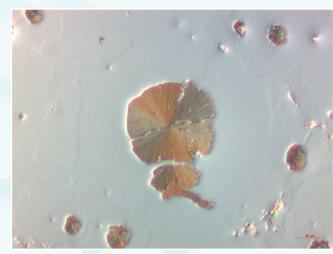


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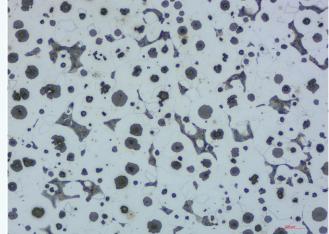
## FINAL RESULT

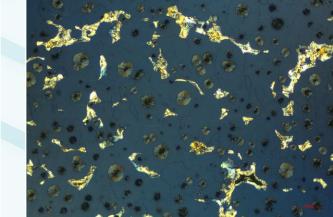






BF, 200x DIC, 200x





Etched with 3% Nital, BF, 200x

Etched with 3% Nital, POL, 200x

